

## EAST Search History

## EAST Search History (Prior Art)

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L3	62	electrostatic adj chuck same first with second with electrode and mesh	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2009/09/24 01:16
S1	7	("20020006680"   "20020043530"   "20030015521"   "5646814").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/09/20 17:21
S4	41	((HIROSHI) near2 (FUJISAWA)).INV.	US-PGPUB; USPAT; USOCR	OR	ON	2007/09/19 19:59
S5	9	((KI NYA) near2 (MIYASHITA)).INV.	US-PGPUB; USPAT; USOCR	OR	ON	2007/09/19 20:00
S6	434	electrostatic adj chuck same first with second with electrode	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/09/21 05:48
S7	47	electrostatic adj chuck same first with second with electrode and mesh	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/09/24 15:49
S8	111	electrostatic adj chuck same first with second with electrode and bipolar	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/09/21 06:15
S9	323	S6 not S8	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/09/21 06:15
S10	297	S9 not S7	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/09/21 06:16
S11	804	(361/234).OCL.S.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2007/09/21 12:39
S12	434	electrostatic adj chuck same first with second with electrode	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/09/21 12:41
S13	674	S11 not S12	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/09/21 12:41

S14	132	electrostatic adj chuck same first with second with electrode and width	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/09/24 15:52
S15	298	electrostatic adj chuck and electrode with width	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/09/24 15:52
S16	10	electrostatic adj chuck and electrode with width with range	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2007/09/24 16:14
S17	2	("6768627").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2007/09/24 16:14
S18	2	("20020109955").PN.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/06/23 15:42
S19	42	((HIROSHI) near2 (FUJISAWA)).INV.	US-PGPUB; USPAT; USOCR	OR	ON	2008/06/23 18:30
S20	11	((KI'NYA) near2 (MIYASHITA)).INV.	US-PGPUB; USPAT; USOCR	OR	ON	2008/06/23 18:30
S21	53	electrostatic adj chuck same first with second with electrode and mesh	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/06/23 18:31
S22	121	electrostatic adj chuck same first with second with electrode and bipolar	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/06/23 18:31
S23	870	(361/234).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2008/06/23 18:31
S24	14	electrostatic adj chuck and electrode with width with range	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/06/23 18:32
S25	54	electrostatic adj chuck same first with second with electrode and bipolar and glass	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/22 10:35
S26	4262941	(electrostatic adj chuck) same (glass) sample workpiece substrate	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/22 10:41
S27	1810	(electrostatic adj chuck) same (glass insulating) same (sample work \$1piece substrate wafer)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/22 10:43

S28	3582	(electrostatic adj chuck) and (glass insulating) with (sample work \$1piece substrate wafer)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/22 10:49
S29	3099	(electrostatic adj chuck) and (glass insulating) near7 (sample work \$1piece substrate wafer)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/22 10:49
S30	3014	(electrostatic adj chuck) and (glass insulating) near6 (sample work \$1piece substrate wafer)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/22 10:50
S31	2096	(electrostatic adj chuck) and (glass insulating) near2 (sample work \$1piece substrate wafer)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/22 10:50
S32	1631	(electrostatic adj chuck) and (glass insulating) near (sample work \$1piece substrate wafer)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/22 10:50
S33	1610	(electrostatic adj chuck) and (glass insulating) near (substrate wafer)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/22 10:52
S34	500	(electrostatic adj chuck) same (glass insulating) near (substrate wafer)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2008/12/22 10:55

**EAST Search History (Interference)**

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**9/ 24/ 2009 1:18:13 AM****C:\Documents and Settings\nieva\My Documents\EAST\Workspaces\10591945\_1(bipolar electrostatic chuck).wsp**